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The Meeting Scene
Technical Program
Call for Papers
Exhibit
Special Events
Career Center
Awards
Tutorials
Information for Authors/Presenters

Home Meetings 2007 Spring Meeting Abstracts

Symposium GG: Ion-Beam-Based Nanofabrication

printer-friendly

April 10 - 12, 2007

MRS 2007 SPRING MEETING

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* Invited paper

SESSION GG1: Ion Beam Nanofab: Tools and Techniques
Chairs: John Baglin and Robert Zimmerman
Tuesday Morning, April 10, 2007
Room 3016 (Moscone West)

8:45 AM *GG1.1
Ion-Beam Projection Techniques for Nanometer-Scale Patterning Ka-Ngo Leung, Plasma and Ion Source Technology Group,, Lawrence Berkeley National Laboratory, Berkeley, California; Nuclear Engineering Department, University of California, Berkeley, California.

Maskless ion beam lithography schemes have been investigated at Lawrence Berkeley National Laboratory (LBNL) for future integrated circuit manufacturing, thin film media patterning, and micromachining. The Maskless Micro-Ion-Beam Reduction Lithography (MMRL) system completely eliminates the first stage of the conventional IPL tool that contains the ion beam illumination column before the